

JHS

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|--|------------------|---------|------------------|
| L3 | 63 | ((wafer or semiconductor or substrate) near15 steam\$8) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8 and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 03:57 |
| L4 | 71 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and steam and ozon\$8 and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 03:57 |
| S21 | 350 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) same (liquid or water or solution or fluid) same ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 01:36 |
| S23 | 722 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 01:41 |
| S25 | 142 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating)) and ozon\$8 and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 02:22 |
| S37 | 320 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8) near15 (inverted or bottom or back or backside)) and (liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 02:42 |

7/15

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|--|------------------|---------|------------------|
| L2 | 350 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) same ((liquid or water or solution or fluid) same ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating))) | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 01:36 |
| L4 | 722 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating))) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 01:41 |
| L6 | 142 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ((chamber or vessel or processor or housing or enclosure) near5 (heat or heated or heater or heating))) and ozon\$8 and "134"/\$.ccls. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 02:22 |
| L18 | 320 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8) near15 (inverted or bottom or back or backside)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 02:30 |
| S13 | 2108 | ((lead near2 angle) or (phase near2 lead)) near15 voltage | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 00:19 |



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|-----|-----|--|--|----|----|------------------|
| S39 | 253 | ((wafer or semiconductor or substrate) near15 (clean\$8 or wash or washing or decontaminat\$8)) near15 ((inverted or bottom or back or backside underneath or beneath or bottomside) near20 (liquid or water or solution or fluid chemical or formulation or solvent or surfactant)) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 02:52 |
| S45 | 341 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) near5 ozon\$8) and "134"/\$.ccls: | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 03:16 |
| S49 | 166 | ((wafer or semiconductor or substrate) near15 (rotate or rotated or rotating spun or spinning or spin or rotor or centrifug\$8)) and ((liquid or water or solution or fluid chemical or formulation or solvent or surfactant) near15 steam) and ozon\$8 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | ON | 2005/12/11 03:29 |